

BEAMLINE	SCIENTIFIC TOPIC	ENERGY RANGE <i>keV</i>	BEAM SIZE <i>H x V</i>	NOMINAL FLUX <i>ph/sec</i>	DETECTORS	SAMPLE ENVIRONMENT <i>& Beamline Support Labs</i>	TECHNIQUE
BM32 <i>IF (French Interface Beamline)</i> SCIENTIST IN CHARGE Jean Sebastien Micha micha@esrf.fr	Chemistry	5 - 30	Microdiffraction laue MIN 0.5 x 0.7 μm^2	Microdiffraction laue $10^6 - 10^7$ <i>0,015%E</i>	INS ▪ 2D detector GMT ▪ 0D: NaI scintillation detector ▪ 2D: CCD camera Photonics Science ImageStar, 1 sCMOS ▪ Rectangular pixel detector ESRF MaxiPix 2 Si 1 CdTe	INS ▪ High temperature furnace (max. 1000°C) ▪ MBE chamber, CBE (gas injection), Auger, RHEED, surface preparation GMT ▪ Mechanical test machine ▪ Furnace in vacuum chamber (25 - 900°C) ▪ Circulating bath (-10 - 70°C) Beamline Support labs ▪ Electronic and mechanical workshop ▪ UHV sample preparation lab	Diffraction
	Env. Sciences & Geosciences		Standard monochromatic MAX 500 x 300 μm^2	Standard monochromatic 5×10^{11}			
	Materials Processing						
	Physics						